

## Supplementary Information

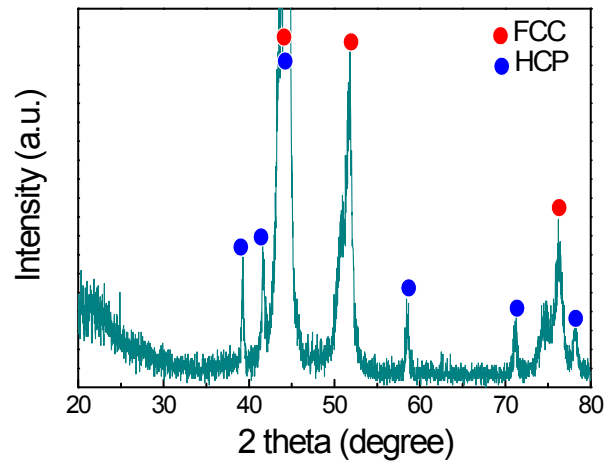
### **Crystalline Structure-Tunable, Surface Oxidation- Suppressed Ni Nanoparticles: Printable Magnetic Colloidal Fluids for Flexible Electronics**

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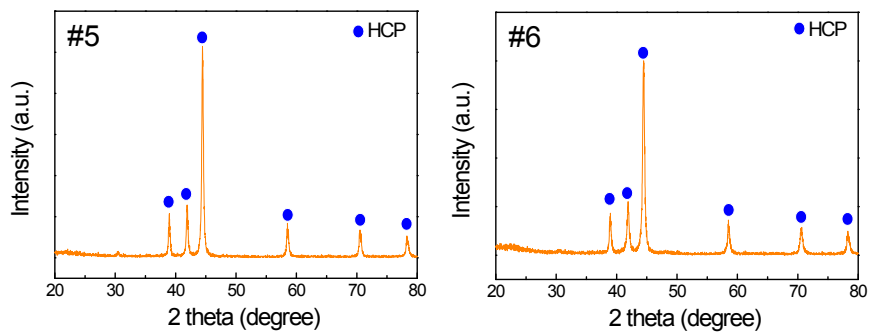
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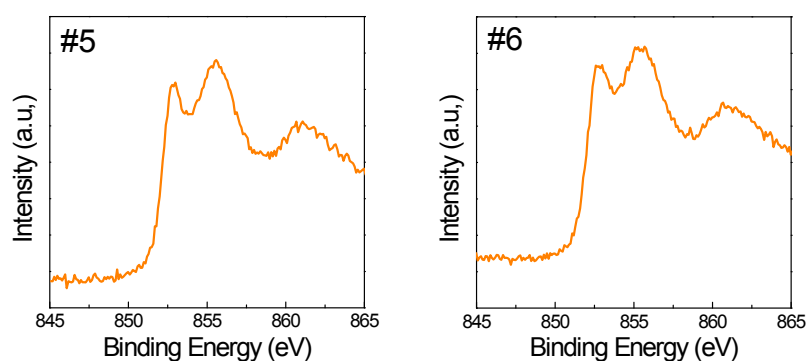
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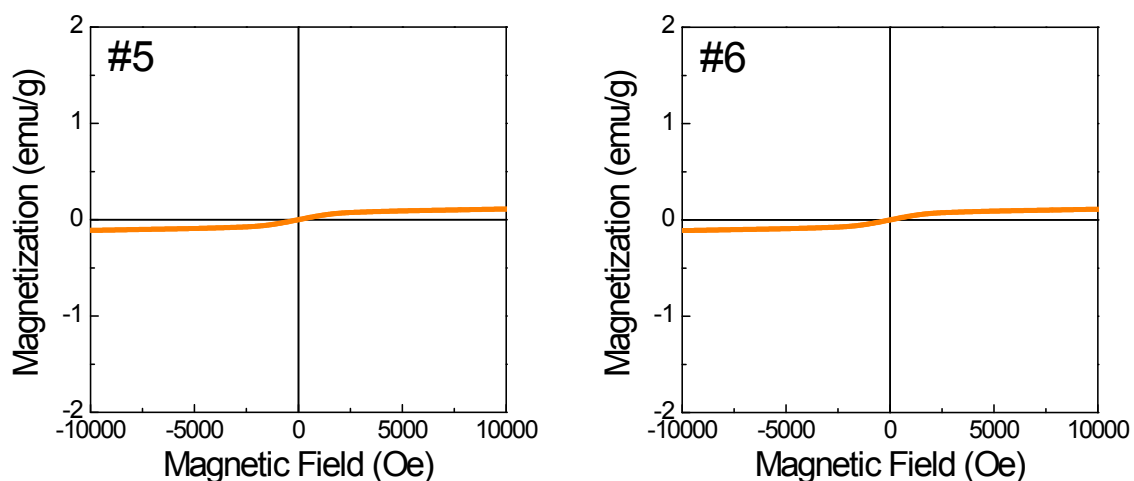
**Figure S1.** X-ray diffraction result for Ni nanoparticles synthesized without oleic acid (sample #1).



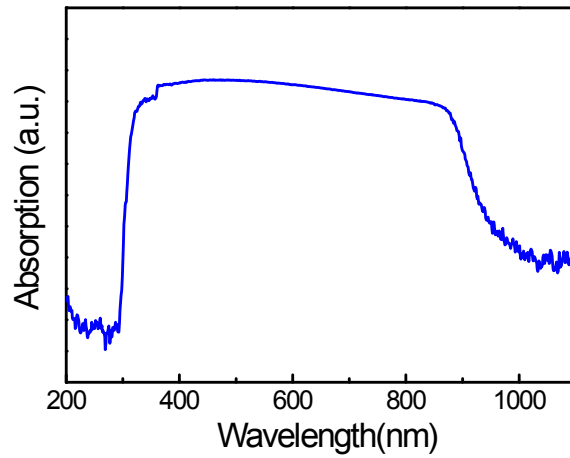
**Figure S2.** (a) X-ray diffraction results for Ni nanoparticles synthesized with different concentrations of phenylhydrazine, 5.5 M (sample #5), and 4.5 M (sample #6), without the presence of oleic acid.



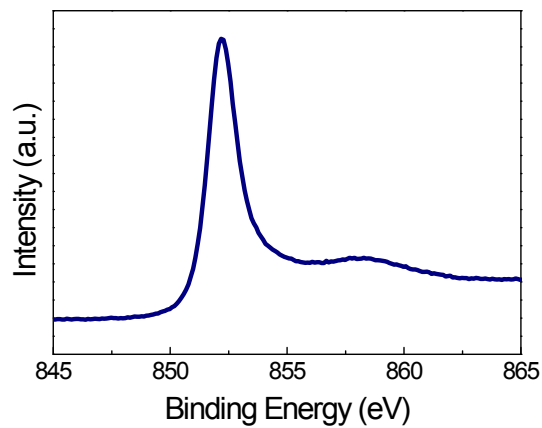
**Figure S3.** X-ray photoelectron spectroscopy spectra of Ni  $2p_{3/2}$  for Ni nanoparticles synthesized with different concentrations of phenylhydrazine, 5.5 M (sample #5), and 4.5 M (sample #6), without the presence of oleic acid.



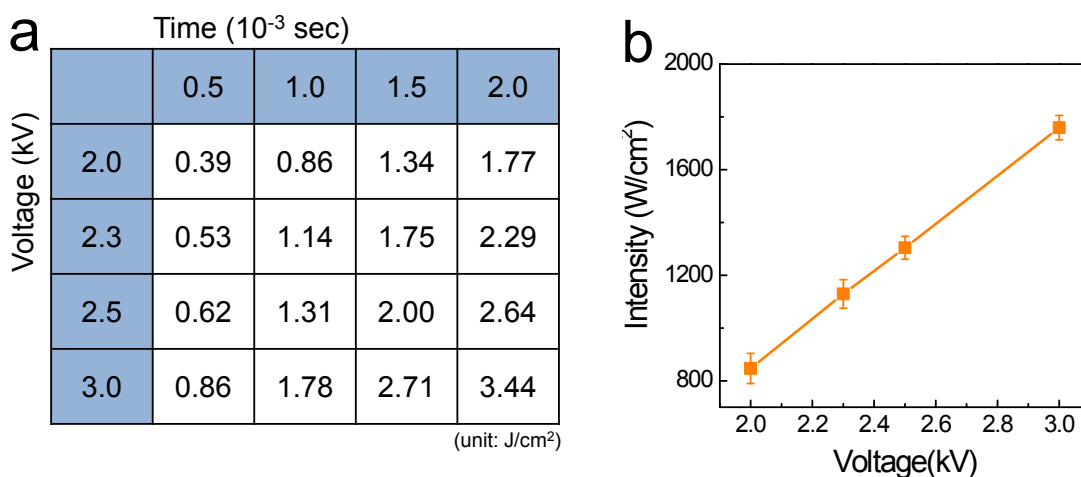
**Figure S4.** Field-dependent magnetization of Ni  $2p_{3/2}$  for Ni nanoparticles synthesized with different concentrations of phenylhydrazine, 5.5 M (sample #5), and 4.5 M (sample #6), without the presence of oleic acid.



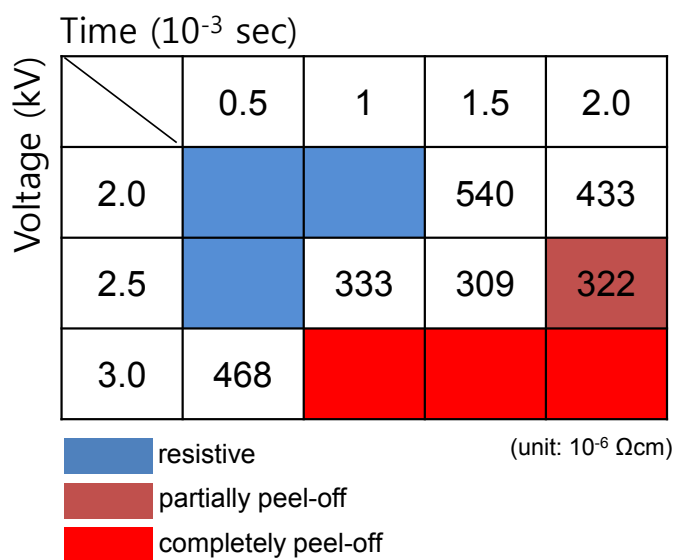
**Figure S5.** UV-visible spectroscopy for the Ni nanoparticle film printed on a glass substrate. The absorption background of the glass substrate was subtracted.



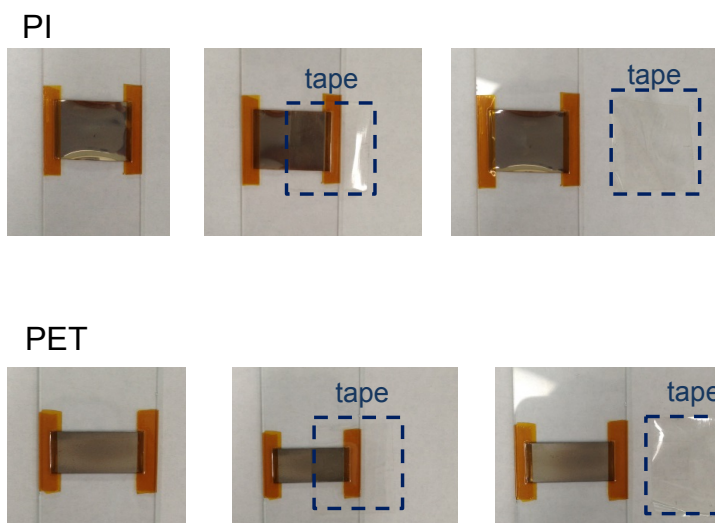
**Figure S6.** X-ray photoelectron spectroscopy spectra of Ni  $2p_{3/2}$  for the Ni nanoparticle film photo-annealed at 2.0 kV for 1.5 msec.



**Figure S7.** (a) The variation of photon energies as a function of voltage and duration time, (b) the variation of intensity depending on the applied voltage in the range of 2.0~3.0 kV.



**Figure S8.** Resistivity evolution in Ni nanoparticle films, patterned on a PI substrate by air-brush printing of Ni nanoparticle suspension, depending on flash-type photonic annealing conditions (voltage and time).



**Figure S9.** The adhesion tests for air brush-printed Ni films on either PI or PET substrate after photonic annealing process. The printed Ni nanoparticle layers were photo-annealed on PI and PET for at 2.5 kV 1.0 msec and at 2.0 kV for 1.5 msec, respectively.